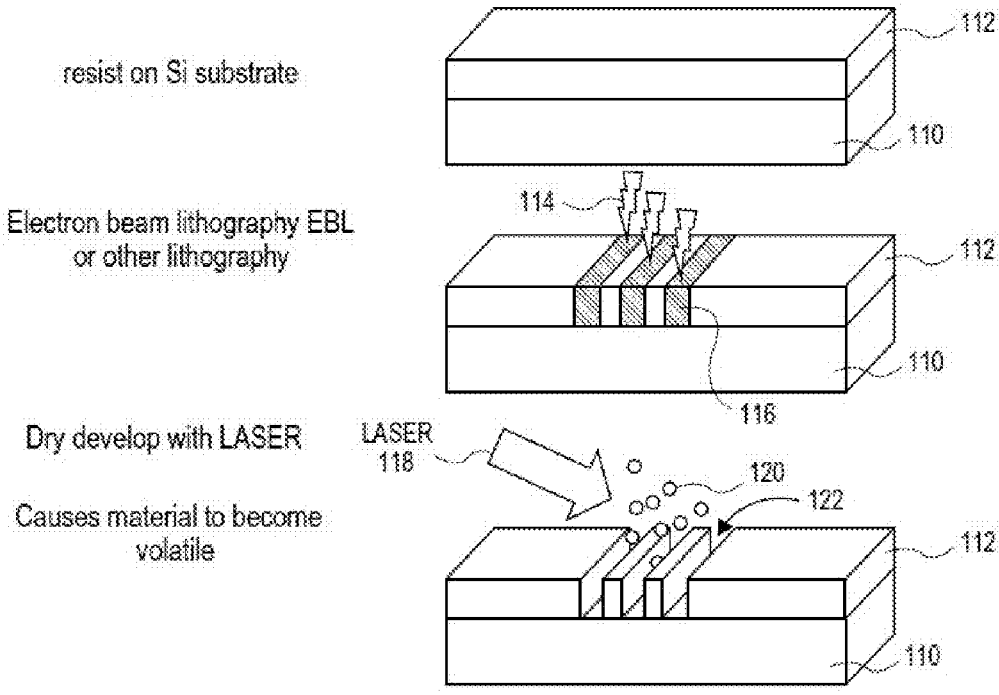
resist on Si substrate
112
110
Electron beam lithography EBL
or other lithography
114
112
110
116
Dry develop with LASER
LASER
118
120
122
Causes material to become
volatile
112
110

FIG. 1